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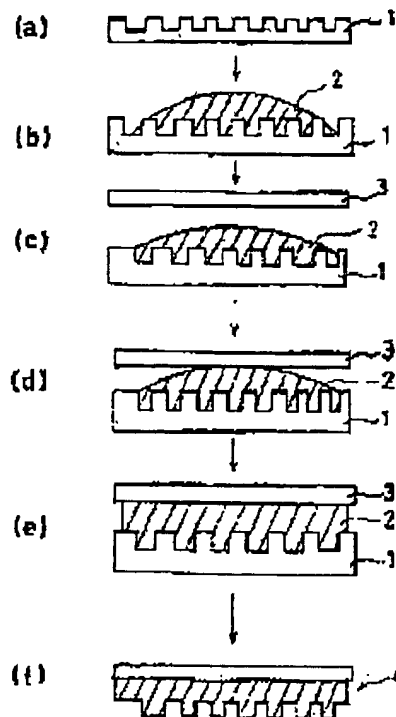
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(54) METHOD OF DUPLICATING MOLDED FORM HAVING UNEVEN PATTERN

(57)Abstract:

PURPOSE: To obtain a duplicating plate capable of being controlled to the dimensions of an uneven pattern required as a product by controlling the temperature and moisture at the time of keeping an original plate in custody and also controlling the dimensions of an uneven pattern of a duplicating plate having a fundamental plate in duplication by a method of 2P having a curing type resin composite used therein.

CONSTITUTION: The duplicating method of 2P having a curing type resin composite 2 employed therein for a molded form 4 having an uneven pattern utilizing a resin plate as an original plate 1 is carried out such that, at first, on the original plate 1 formed with an uneven pattern, a curing type resin composite 2 is permitted to drop, and a fundamental plate 3 is lamination- laid on the resin composite 2 to be pressed. Next, by irradiating ionization radiation rays such as ultraviolet rays from the side of the fundamental plate 3 in order to cure the resin composite 2, and the resin composite 2 and fundamental plate 3 integrated with each other are separated from the original plate 1 side so as to duplicate the molded product 4. At the time of effecting duplication by a method of 2P having the curing type resin composite 2 used therein, the dimensions of an uneven pattern of duplicated plate having the fundamental plate 3 is controlled by adjusting the temperature and moisture



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during the period of having custody of the original plate 1.